INFORMATION DISCLOSURE CITATION *(Use several sheets if necessary)*	Docket Number (Optional) TWI-12810	Application Number NEW
	Applicant(s) Allan Rosencwaig	
	Filing Date HEREWITH	Group Art Unit UNKNOWN

U.S. PATENT DOCUMENTS

*Examiner Initial	Ref	Document Number	Date	Name	Class	Subclass	Filing Date
	A	4,999,014	03/12/1991	Gold et al	356	382	05/04/1989
	B	5,042,951	08/27/1991	Gold et al	356	369	09/19/1989
	C	5,131,752	07/21/1992	Yu et al	356	369	06/28/1990
	D	5,620,556	04/15/1997	Henck	438	8	02/08/1995
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OTHER DOCUMENTS

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	G	G.M.W. Kroesen et al., "Nonintrusive wafer temperature measurement using *in situ* ellipsometry," *J. Appl. Phys.*, Vol. 69, No. 5, 1 March 1991, pp. 3390 – 3392.
	H	C.T. Yu et al., "Using In Situ Ellipsometry for Film Thickness Endpoint Control," *Semiconductor International*, May 1991, pp. 166 – 169.
	I	M. Haverlag et al., "Ellipsometric study of silicon surface damage in electron cyclotron resonance plasma etching using CF_4 and SF_6," *Appl. Phys. Lett.*, Vol. 16, No. 24, 14 December 1992, pp. 2875 – 2877.
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	K	N. Blayo et al., "Ultraviolet-visible ellipsometry for process control during the etching of submicrometer features," *J. Opt. Soc. Am. A*, Vol. 12, No. 3, March 1995, pp. 591 – 599.
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	M	S.A. Henck, "*In situ* real-time ellipsometry for film thickness measurement and control," *J. Vac. Sci. Technol. A*, Vol. 10, No. 4, Jul/Aug 1992, pp. 934-938.
	N	R. W. Collins, "Automatic rotating element ellipsometers: Calibration, operation, and real-time applications," *Rev. Sci. Instrum.*, Vol. 61, No. 8, August 1990, pp. 2029 – 2062.
	O	Copy of U.S. Patent Application No. 09/575,295, filed May 29, 2000, by inventors Lanhua Wei et al., entitled "Monitoring Temperature and Sample Characteristics Using a Rotating Compensator Ellipsometer," 17 pages of application, and 3 pages of informal drawings.

Examiner: K. Zan	Date Considered 8-19-03

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.